

Abstract

To produce substrates with functional layers which have high optical properties and/or a high surface smoothness, in particular a low turbidity and significantly lower roughness, the invention provides a sputtering process for coating a substrate with at least one functional layer, the sputtering process for coating with a functional layer being interrupted at least once by the application of an intermediate layer with a thickness of less than 20 nm, as well as coated substrates produced by the process.